WHAT IS CLAIMED IS:

1. A low-reflectance conductive film characterized in that said low-reflectance conductive film comprises at least two films which are a conductive film comprising conductive fine particles and a low-refraction film formed on said conductive film, having a lower refractive index than said conductive film, and that said conductive film comprises a resistance-lowering material.

2. The low-reflectance conductive film according to Claim 1, wherein said conductive fine particles are fine particles of tin-doped indium oxide or fine particles of antimony-doped tin oxide.

3. The low-reflectance conductive film according to Claim 1, wherein said resistance-lowering material is a sulfur compound and/or titanium oxide.

4. The low-reflectance conductive film according to Claim 1, wherein said resistance-lowering material is a sulfur compound, and said sulfur compound is at least one kind selected from the group consisting of α-lipoic acid, α-lipoamide, thiodipropionic acid, sodium thiosulfate, thiourea, and sodium thioglycollate.

5. The low-reflectance conductive film according to Claim 1, wherein said resistance-lowering material is a sulfur compound, and the content of said sulfur compound in said conductive film, when converted to the mass of sulfur in said conductive film, is from 0.1 to 10 mass% to the conductive fine particles in the conductive film.

6. The low-reflectance conductive film according to Claim 1, wherein said resistance-lowering material is titanium oxide, and the content of said titanium oxide in the conductive film is from 0.1 to 20 mass% to the conductive fine particles in the conductive film.

7. The low-reflectance conductive film according to Claim 1, wherein said conductive film has a film thickness of from 5 to 200 nm, and said low-refraction film has a film thickness of from 5 to 150 nm.

8. A colored low-reflectance conductive film according to Claim 1, wherein a colored film containing therein a coloring component is formed on a side opposite to the low refraction film of said conductive film.

9. The colored low-reflectance conductive film according to Claim 8, wherein said coloring component is carbon black or titanium black.

10. The colored low-reflectance conductive film according to Claim 8, wherein said colored film has a film thickness of from 5 to 200 nm.

11. A coated article comprising a substrate on which there is formed said low-reflectance conductive film as defined in Claim 1.

12. A display apparatus wherein said coated article as defined in Claim 11 is incorporated so as to position said low-reflectance conductive film or said colored low-reflectance conductive film at an external surface thereof.

13. An X-coating liquid comprising a solvent, conductive fine particles, and a resistance-lowering material.

14. A conductive film forming coating liquid as defined in Claim 13, wherein the concentration of said conductive fine particles is from 0.01 to 20 mass% to the total mass of said coating liquid, said resistance-lowering material is a titanium oxide source, and the content of said titanium oxide source, when converted to the mass of titanium oxide, is from 0.1 to 20 mass% to the conductive fine particles.

15. A low-refraction film forming coating liquid comprising a solvent, a silicon compound, and a resistance-lowering material.

16. The low-refraction film forming coating liquid according to Claim 15, wherein said silicon compound is a silicon alkoxide, with the content of said silicon alkoxide being in an amount of from 0.1 to 30 mass% in terms of the solid component concentration of SiO_2 to the total amount of said low-refraction film forming coating liquid, and said resistance-lowering material is a sulfur compound, with the content of said sulfur compound being in an amount of from 0.01 to 1.5 mass% to the total amount of said low-refraction film forming coating liquid.

17. The low-refraction film forming coating liquid according to Claim 15, wherein said silicon compound is a silicon alkoxide, with the content of said silicon alkoxide being in an amount of from 0.1 to 30 mass% in

terms of the solid component concentration of SiO_2 to the total amount of said low-refraction film forming coating liquid, and said resistance-lowering material is a titanium oxide source, with the content of said titanium oxide source, when converted into the amount of titanium oxide, being in an amount of from 0.01 to 1.0 mass% to the total amount of said low-refraction film forming coating liquid.

18. A low-reflectance conductive film manufacturing method for forming a low-reflectance film by coating onto a substrate a conductive film forming coating liquid which contains conductive fine particles, and then coating a low-refraction film forming coating liquid which contains a resistance-lowering material.

19. A colored low-reflectance film manufacturing method according to Claim 18 for forming a colored low-reflectance film by coating onto a substrate a colored film forming coating liquid which contains a coloring component, prior to the coating of said conductive film forming coating liquid.

20. A low-reflectance conductive film manufacturing method characterized by coating onto a substrate a conductive film forming coating liquid which contains conductive fine particles, then coating a low-refraction film coating liquid, thereby forming a low-reflectance conductive film, and irradiating said low-reflectance conductive film with a light having energy greater than

the band gap of said conductive particles, thereby reducing the surface resistance value of said low-reflectance film in comparison with the case where the irradiation of said light is not carried out.

21. A low-reflectance conductive film manufacturing method for forming a low-reflectance conductive film by coating onto a substrate a conductive film forming coating liquid which contains conductive fine particles, then coating a low-refraction film forming coating liquid, thereby forming the low-refraction film, characterized in that said conductive film forming coating liquid and/or said low-refraction film forming coating liquid contains a titanium oxide source, and the surface resistance value of said low-reflectance film is reduced by irradiating said low-reflectance conductive film with light having energy greater than the band gap of titanium oxide, in comparison with the case where the irradiation of said light is not carried out.